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## (54) CLEANING METHOD OF FILTER MEMBRANE MODULE

### (57)Abstract:

**PROBLEM TO BE SOLVED:** To obtain a cleaning method of a filter membrane module capable of sufficiently removing an adsorbed material to the filter membrane, improving cleaning effect, reducing the consumption of a liquid chemical, cleaning with the liquid chemical for a short time and decreasing cleaning cost in a liquid chemical cleaning process of the filter membrane.

**SOLUTION:** In the cleaning method of the filter membrane module 11 for recovering the water permeability by cleaning the filter membrane module 11 degraded in water permeability of a membrane purifying system 10 of water with the liquid chemical, at least one point of time before and after the liquid chemical is supplied to the filter membrane module 11 or at the both point of time, a gas pressurizing process for pressurizing a gas from the permeation side of the filter membrane of the filter membrane module 1 at  $\geq 20$  kPa to below the bubble point is provided for 1-5 min.

